

Table of Contents

Preface

PECVD of Silicon Dioxide from TEOS/Oxygen Mixtures T.S. Cale and G.B. Raupp	1
Analysis and Design of Plasma Chemical Reactions Based on Quantum Chemical Methods K. Sato	17
Advanced Simulation of Dry Etching Process Technology J. Pelka	25
Anisotropic ECR Plasma Etching with Low-Energy Ions Y. Tobinaga, T. Miyano, K. Fujimoto, M. Fujito and H. Fujiwara	39
High-Rate Sputtering with Electron Cyclotron Resonance and Electric-Mirror Excitation M. Matsuoka	55
Modified ECR Plasma Deposition S. Nakamura, T. Akahori and S. Nakayama	79
DC Saddle-Field Plasma-Enhanced Vapour Deposition R.V. Kruzelecky and S. Zukotynski	89
Theoretical Characterization of Electron Energy Distribution Function in RF Plasmas M. Capitelli, G. Capriati, M. Dilonardo, C. Gorse and S. Longo	107
Ion Energy Distributions and Sidewall Profiles in Reactive Ion Etching P.W. May, D.P. Field, D.F. Klemperer and Y.P. Song	121
Dissipative Structures and Nonequilibrium Phenomena in Plasma-Surface Interaction Y.L. Khait	133
Source of Atomic Oxygen and its Application to Material Oxidation A.M. Pointu, M. Touzeau and O. Guymont	159
Practical Applications of In-Situ Plasma-Etching Diagnostic Techniques D.J. Thomas, P. Southworth, M.C. Flowers, N.J. Dartnell, R. Greef and Y. Liu	171
Laser-Aided Diagnostics of Processing Plasmas K. Muraoka and M. Maeda	191
Radical Kinetics in Processing Plasmas: Optical Diagnostics of Gas Phase and Surface Reactions J.P. Booth and G. Hancock	219
Negatively Charged Particles in Fluorocarbon RF Etch Plasmas: Density Measurements Using Microwave Resonance and the Photodetachment Effect M. Haverlag, A. Kono, G.M.W. Kroesen and F.J. de Hoog	235
Biased Electron Cyclotron Resonance Chemical-Vapor Deposition of Silicon Dioxide Inter-Metal Dielectric Thin Films P. Shufflebotham, M. Weise, D. Pirkle and D. Denison	255
TEOS-Based Oxides: Deposition Dependent Properties M. Saran and I. Emesh	269
Plasma Enhanced Chemical Vapor Deposited Silicon and Silicon Dioxide Films for Indium Phosphide MISFET Technology M. Shokrani and V.J. Kapoor	285
Physical and Electrical Properties of Silicon Nitride and Oxynitride Films Prepared by Plasma Enhanced CVD J. Vuillod	301
Preparation and Properties of PECVD Silicon Nitride Films from $\text{SiH}_4 + \text{NH}_3$ and/or NF_3 and $\text{SiF}_4 + \text{NH}_3$ Gas Mixtures C. Gómez-Aleixandre, O. Sanchez and J.M. Albella	319
Bonding Configuration and Defects in Glow-Discharge Amorphous $\text{SiN}_x\text{:H}$ Films Deposited at 300°C and 500°C S. Hasegawa, Y. Amano, L. He, T. Inokuma and Y. Kurata	335
Doped Glasses for ULSI-Technology: Integration of Molecular Engineering and Plasma-CVD H. Treichel, J. v. Tomkewitsch and O. Spindler	359

Growth Processes and Defect Densities in Hydrogenated Amorphous Silicon Alloys J. Robertson	381
Sputter Deposition of Thin Films for High Mobility Poly-Si TFT Fabrication T. Serikawa	387
Ion Assisted Thin Film Growth in Dual Microwave/Radio Frequency Plasmas L. Martinu and M.R. Wertheimer	405
High Powered Pulsed Plasma Enhanced Deposition of Thin Film Semiconductor and Optical Materials I.P. Llewellyn, K.J.A. Sheach and R.A. Heinecke	421
Plasma-Enhanced Chemical Vapour Deposition of Coatings in the System Ti-B-N J. Laimer, H. Karner, H. Störi and P. Rödhammer	439
Plasma-Enhanced Metalorganic Chemical Vapor Deposition for High Temperature Superconducting Thin Film K. Ebihara and T. Ikegami	457
Low Pressure and Low Temperature Synthesis of Diamond Films Using Magneto-Microwave Plasma CVD J. Wei, H. Kwarada and A. Hiraki	465
Thermal Plasma Chemical Vapor Deposition J.V.R. Heberlein and E. Pfender	477
Thermally Sprayed Coatings for Electrical and Electronic Applications L. Pawlowski and P. Fauchais	497
ECR Plasma Etching Technology for ULSI S. Samukawa	521
Evaluation of Substrate Degradation in Plasma Etch Processes Using Thermal Wave Analysis M. Engelhardt	541
Plasma Etching of Patterned Tungsten S. Franssila	565
Microwave Plasma Oxidation of Silicon S. Kimura	583
Hydrogen Interaction with Disordered Silicon S. Ashok and K. Srikanth	603
Damage Assessment of Dry Etched III-V Semiconductors for Nanoelectronics R. Cheung	619
Reactive Ion Beam Etching for Microcavity Surface Emitting Laser Fabrication: Technology and Damage Characterization A. Matsutani, T. Tadokoro, F. Koyama and K. Iga	641
Alkane Plasma Etching of Gallium Arsenide V.J. Law, M. Tewardt, S.G. Ingram and G.A.C. Jones	659
Effects of ECR-Plasma Excitation in GaAs MBE Growth T. Shibata, N. Yamamoto, N. Kondo, Y. Nanishi and M. Fujimoto	689
Plasma Treatment of Polymers for Improved Adhesion Properties S. Nowak and O.M. Küttel	705
Study of Dry Development in Terms of Resist and Development Method N. Abe and T. Motoyama	727